L Number	Hits	S arch Text	DB	Time stamp
	91	(pattern same (h ld or h lding or support or	USPAT;	2004/02/03
		supp rting) am mask same (alignment	US-PGPUB;	16:57
		adj mark) same exp sur )	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	6	(pattern same (hold or holding or support or	USPAT;	2004/02/03
		supporting) same mask same (first adj	US-PGPUB;	16:57
		alignment adj mark) same exposure)	EPO; JPO;	
		_	DERWENT;	
			IBM_TDB	
_	5	(pattern same (hold or holding or support or	USPAT;	2004/02/03
		supporting) same mask same (first adj	US-PGPUB;	16:58
		alignment adj mark) same (second adj	EPO; JPO;	
		alignment adj mark) same exposure)	DERWENT;	
			IBM_TDB	
	5	((pattern same (hold or holding or support	USPAT;	2004/02/03
		or supporting) same mask same (first adj	US-PGPUB;	16:59
		alignment adj mark) same (second adj	EPO; JPO;	
		alignment adj mark) same exposure)).clm	DERWENT;	
			IBM_TDB	
-	5	((pattern same (hold or holding or support	USPAT;	2004/02/03
		or supporting) same mask same (first adj	US-PGPUB;	16:59
		alignment adj mark) same (second adj	EPO; JPO;	
		alignment adj mark) same exposure)).clm	DERWENT;	
		and beam	IBM_TDB	
-	5	((pattern same (hold or holding or support	USPAT;	2004/02/03
		or supporting) same mask same (first adj	US-PGPUB;	17:00
		alignment adj mark) same (second adj	EPO; JPO;	
		alignment adj mark) same exposure)).clm	DERWENT;	
		and ((electron or (charge near particle)) adj	IBM_TDB	
	_	beam)		0004/00/00
-	5	((pattern same (hold or holding or support	USPAT;	2004/02/03
		or supporting) same mask same (first adj	US-PGPUB;	17:00
		alignment adj mark) same (second adj	EPO; JPO;	
		alignment adj mark) same exposure)).clm	DERWENT;	
		and ((electron or (charge near particle)) adj	IBM_TDB	
	0	beam).ti,ab,clm.	USPAT;	2004/02/03
	U	((pattern same (hold or holding or support or supporting) same mask same (first adj	US-PGPUB;	17:00
		1		17:00
	·	alignment adj mark) same (second adj	EPO; JPO; DERWENT;	
		alignment adj mark) same exposure)).clm.		
		and ((electron or (charge near particle)) adj beam).ti,ab,clm.	IBM_TDB	
_	1	((pattern same (hold or holding or support	USPAT;	2004/02/04
-	•	or supporting) same mask same (first adj	US-PGPUB;	10:37
		alignm nt adj mark) same (s ond adj	EPO; JPO;	.0.07
		alignm nt adj mark) same (s ond adj alignm nt adj mark) same xp sure)).clm.	DERWENT;	
		and ((electr n r ( harge near particle)) adj	IBM_TDB	
		beam)	.51.55	

4				
-	76	((h ld or holding or support or upporting) near5 (alignm nt n ar mark)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:44
-	15	((h ld rh lding or supp rt or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:46
-	4	((hold or holding or support or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:48
-	1	((hold or holding or support or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:48
-	1	(charge near particle)) near beam) ((hold or holding or support or supporting) near10 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and ((electron or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:49
-	4	(charge near particle)) near beam) ((hold or holding or support or supporting) and (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:49
-	1	(charge near particle)) near beam) mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50
-	1	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50
-	10	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50
	1	1	,	i

•	10	mask.clm. and mask.ab. and (first adj	USPAT;	2004/02/04
		alignm nt adj mark).clm. and (sec nd adj	US-P PUB;	10:51
		alignment adj mark).clm. and ((   ctron or	EPO; JPO;	
		(charge near particl )) near beam) and	DERWENT;	
		(mask sam patt rn am (alignment adj mark))	IBM_TDB	
-	6	mask.clm. and mask.ab. and (first adj	USPAT;	2004/02/04
		alignment adj mark).clm. and (second adj	US-PGPUB;	10:51
		alignment adj mark).clm. and ((electron or	EPO; JPO;	
		(charge near particle)) near beam) and	DERWENT;	
		(mask same pattern same (alignment adj	IBM_TDB	
		mark)).clm.		_